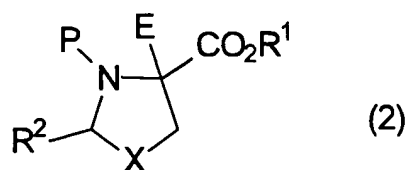


Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claim 1 (Original): A' process for preparing compounds of the general formula (2)



where

X is S or O and

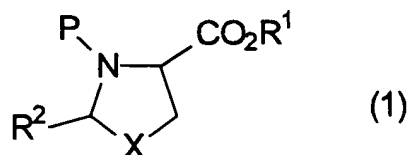
R¹ is selected from the group comprising hydrogen, metals of the first or second main group, linear or branched C₁-C₁₂-alkyl, C₆-C₁₅-aryl or C₇-C₂₁-aralkyl radicals, dialkylsilyl and trialkylsilyl, dialkylarylsilyl, diarylalkylsilyl, triarylsilyl radicals, and the organic radicals of the silyl radicals are in turn selected from C₁-C₁₂-alkyl and C₆-C₁₅-aryl radicals and

R^2 is selected from the group comprising linear or branched C_1 - C_{12} -alkyl, C_6 - C_{15} -aryl and C_7 - C_{21} -aralkyl radicals and

P is an amino protecting group and

E is a radical selected from the group comprising optionally halogen, cyano, nitro or ester group-substituted, linear or branched C_1 - C_{12} -alkyl, C_3 - C_{10} -alkenyl, C_6 - C_{15} -aryl and C_7 - C_{21} -aralkyl radicals, or is an acyl or formyl group,

comprising adding a base to a reaction mixture comprising a compound of the general formula (1)



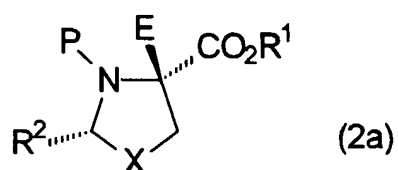
and an electrophile $E-Y$

where

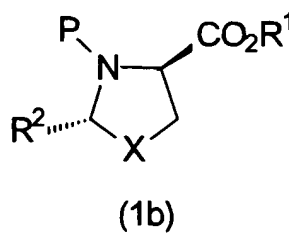
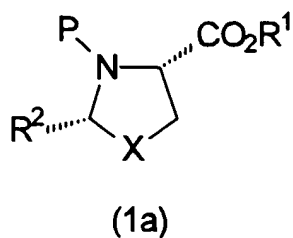
Y is a leaving group,

and carrying out the reaction at a temperature of greater than - 40°C.

Claim 2 (Currently Amended): ~~The process of claim 1,~~
~~wherein~~ A process for preparing optical isomers in the
configuration of the general formula (2a)



~~are prepared~~ using optical isomers of the general formulae (1a)
or (1b) in pure form or as mixtures



where

X is S or O and

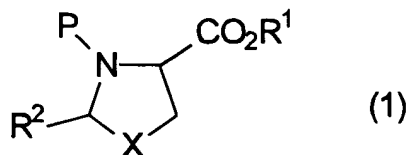
R¹ is selected from the group comprising hydrogen, metals of the first or second main group, linear or branched C₁-C₁₂-alkyl, C₆-C₁₅-aryl or C₇-C₂₁-aralkyl radicals, dialkylsilyl and trialkylsilyl, dialkylarylsilyl, diarylalkylsilyl, triarylsilyl radicals, and the organic radicals of the silyl radicals are in turn selected from C₁-C₁₂-alkyl and C₆-C₁₅-aryl radicals and

R² is selected from the group comprising linear or branched C₁-C₁₂-alkyl, C₆-C₁₅-aryl and C₇-C₂₁-aralkyl radicals and

P is an amino protecting group and

E is a radical selected from the group comprising optionally halogen, cyano, nitro or ester group-substituted, linear or branched C₁-C₁₂-alkyl, C₃-C₁₀-alkenyl, C₆-C₁₅-aryl and C₇-C₂₁-aralkyl radicals, or is an acyl or formyl group,

comprising adding a base to a reaction mixture comprising a compound of the general formula (1)



and an electrophile E-Y

where

Y is a leaving group,

and carrying out the reaction at a temperature of greater than -40°C.

Claim 3 (Original): The process of claim 1, wherein P is selected from the group consisting of alkyl, formyl, acyl, oxycarbonyl, sulfonyl, sulfenyl and silyl radicals.

Claim 4 (Original): The process of claim 1, wherein Y is selected from the group consisting of halogens, tosylates, azides, hydrazides, dialkylamides and sulfonates.

Claim 5 (Original): The process of claim 1, wherein the base is an alkali metal amide.

Claim 6 (Currently Amended): The process of claims 1, wherein E-Y is methyl iodide or dimethyl sulfate.

Claim 7 (Original): The process of claim 1, wherein the process is carried out at a temperature of from -30°C to + 30°C.

Claim 8 (Original): The process of claim 1, wherein R¹ is selected from the group consisting of hydrogen, methyl, ethyl, n-propyl, isopropyl, n-butyl, tert-butyl, phenyl, benzyl, trimethylsilyl, triethylsilyl and tributylsilyl.

Claim 9 (Original): The process of claim 1, wherein R² is selected from the group consisting of methyl, ethyl, n-propyl, isopropyl, n-butyl, tert-butyl, cyclohexyl, phenyl, tolyl, naphthyl and benzyl.

Claim 10 (New): The process of claim 2, wherein P is selected from the group consisting of alkyl, formyl, acyl, oxycarbonyl, sulfonyl, sulfenyl and silyl radicals.

Claim 11 (New): The process of claim 2, wherein Y is selected from the group consisting of halogens, tosylates, azides, hydrazides, dialkylamides and sulfonates.

Claim 12 (New): The process of claim 2, wherein the base is an alkali metal amide.

Claim 13 (New): The process of claim 2, wherein E-Y is

methyl iodide or dimethyl sulfate.

Claim 14 (New): The process of claim 2, wherein the process is carried out at a temperature of from -30°C to $+ 30^{\circ}\text{C}$.

Claim 15 (New): The process of claim 2, wherein R^1 is selected from the group consisting of hydrogen, methyl, ethyl, n-propyl, isopropyl, n-butyl, tert-butyl, phenyl, benzyl, trimethylsilyl, triethylsilyl and tributylsilyl.

Claim 16 (New): The process of claim 2, wherein R^2 is selected from the group consisting of methyl, ethyl, n-propyl, isopropyl, n-butyl, tert-butyl, cyclohexyl, phenyl, tolyl, naphthyl and benzyl.